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| U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified) | | Docket No. AMAT/6198 | Serial No. 10/016,300 |
| LIST OF PATENTS AND PUBLICATIONS CITED BY APPLICANT | | Applicant Tzu, et al. | Confirmation No.: |
| (Use several sheets if necessary) | | Filing Date December 12, 2001 | Group 163 Unknown |
| | Examiner <u>Unknown</u> <u>ZERVIGON</u> | | |

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| | | Examiner <u>Unknown</u> <u>Zervigon</u> | | | | |

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| (Use several sheets if necessary) | | Filing Date December 12, 2001 | Group /763 Unknown |
| | Examiner <u>Unknown</u> <u>Zervigon</u> | | |

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| | Examiner <u>Unknown</u> <u>Bension</u> | | |

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| | Examiner Unknown <i>Zervigon</i> | | |

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